

OPTIMIZED PLACEMENT OF SUB-RESOLUTION ASSIST FEATURES WITHIN TWO-DIMENSIONAL ENVIRONMENTS

Abstract

A method of creating a photomask layout for projecting an image of an integrated circuit design comprises creating a layout of spaced integrated circuit shapes to be projected via the photomask, determining bisectors between adjacent ones of the spaced integrated circuit shapes, and creating sub-resolution assist features along at least some of the bisectors between the adjacent ones of the spaced integrated circuit shapes. The bisectors may be determined by creating Voronoi cells around the spaced integrated circuit shapes. Preferably, the adjacent ones of the spaced integrated circuit shapes are parallel to each other and the sub-resolution assist features along the bisectors are parallel to the spaced integrated circuit shapes.